

Dominant formation and quenching kinetics of electron beam pumped Xe₂Cl

G. Marowsky

Max-Planck-Institut für Biophysikalische Chemie, Abteilung Laserphysik, D-3400 Göttingen, Federal Republic of Germany

G. P. Glass, M. Smayling, F. K. Tittel, and W. L. Wilson

Rice Quantum Institute, Chemistry and Electrical Engineering Departments, Rice University, Houston, Texas 77001

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Processes leading to the production and removal of the triatomic excimer Xe₂Cl* subsequent to short duration electron beam excitation of Ar/Xe/CCl₄ mixtures have been investigated. The radiative lifetime of Xe₂Cl* has been measured to be 135 (± 70) ns. Formation of the excimer has been shown to occur principally via a termolecular reaction involving XeCl*. Rate constants for the formation and collisional quenching of Xe₂Cl* by CCl₄, Xe, and Ar have been determined.

I. INTRODUCTION

There has been a considerable interest in triatomic excimers as media for tunable lasers in the visible and UV wavelength region for a variety of applications. Broadband continuous emission due to bound-free transitions of Rg₂X* trimers has been observed from several electron beam excited high pressure rare gas-halide mixtures.¹⁻⁴ However, while the broadband nature of these transitions offers wavelength tunability, the effective gain of the triatomic excimers is low compared to that of the molecular diatomic excimers. To date two molecules (Xe₂Cl⁵ and Kr₂F⁶) have demonstrated laser action centered at 520 and 436 nm, respectively. The stimulated emission occurs for transitions between bound ionic excited states and repulsive covalent lower states.¹ The bound-free nature of the laser transition prevents population buildup in the lower laser level. The kinetics of these lasers is not completely understood for electron beam excited rare gas-halide mixtures. However, kinetic studies of Xe₂Cl and Kr₂F using synchrotron radiation excitation and photolytic pumping have recently been reported.⁷⁻¹⁰ In this paper we discuss the formation and quenching kinetics of Xe₂Cl* based on fluorescence studies of high pressure Ar/Xe/CCl₄ mixtures irradiated by short duration electron beam pulses. This information can be used to evaluate and predict the performance characteristics of the Xe₂Cl laser.

II. EXPERIMENTAL APPARATUS AND TECHNIQUES

In order to obtain the high pumping powers needed to achieve laser action of triatomic excimers, electron beam excitation was used to form excited buffer gas (argon) atoms and ions. These species, in turn, react with the rare gas and halogen donors to create the excimers. The experiments were carried out in a stainless steel cell attached to the field emission diode of an electron beam accelerator (Physics International Pulserad 110). A beam of 1 MeV electrons with a pulse duration of 10 ns (FWHM) was injected transversely into the reaction cell through a 50 μ thick titani-

um anode foil over an area of 1 × 10 cm, with a current density of ~ 100 A/cm² at the optical axis. Details of the apparatus have been reported previously in Ref. 11, and are shown in Fig. 1.

The rare gases used in these studies were of research grade, and were turbulently mixed. A considerable decrease of emission intensity was observed if successive shots were taken with the same mixture. In order to assure good shot to shot reproducibility, a fresh gas mixture was prepared for each measurement.

All of the measurements were made with computer aided instrumentation. Temporal behavior of both fluorescence and laser output was obtained with a fast photodiode (ITT F4000-S5), and recorded with a transient digitizer (Tektronix R7912). Interference/color glass filters defined the spectral region of interest. Simultaneously, time integrated, spectrally resolved data were recorded with a calibrated optical multichannel analyzer (PAR OMA1). Both the OMA and the

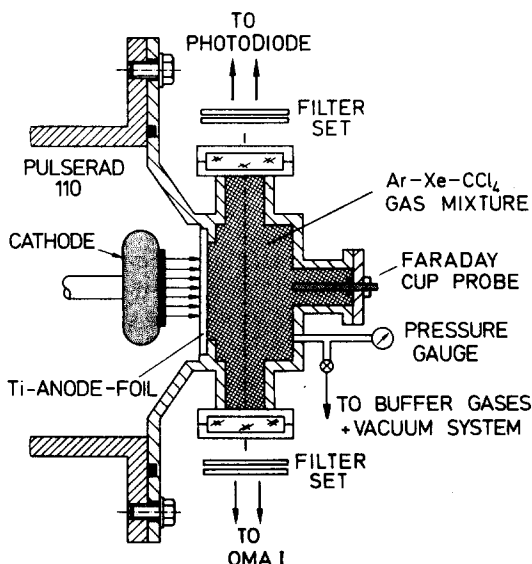


FIG. 1. Diagram of the electron beam pumped reaction cell.

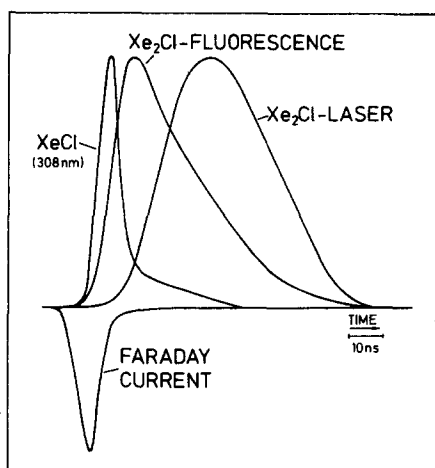


FIG. 2. Typical temporal characteristics of XeCl and Xe₂Cl fluorescence and laser pulses. The electron beam excitation pulse as monitored by a Faraday current probe is also indicated.

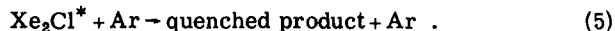
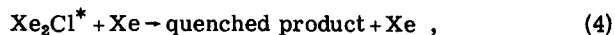
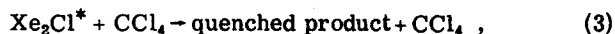
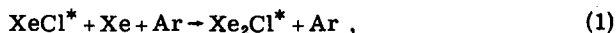
transient digitizer were interfaced to a DEC PDP 11/23 minicomputer system. Subsequent data reduction and feature extraction were accomplished with computer routines developed for these studies.

The temporal behavior of Xe₂Cl fluorescence and laser emission is shown in Fig. 2. This figure depicts the normalized, spectrally resolved photodiode signals of Xe₂Cl fluorescence and laser output at 500 nm. The fluorescence of XeCl (*B* → *X*) at 308 nm and the electron beam pulse are also shown. An intracell resonator, consisting of two high reflectivity dielectric mirrors, was used in the laser experiments.⁵

A typical example of a time integrated fluorescence spectrum obtained with the OMA 1 is shown in Fig. 3. In the case of XeCl both an intense, narrow linewidth *B* → *X* transition and a broadband *C* → *A* transition are observed at 308 and 345 (± 20 nm), respectively. Xenon pressures in excess of 100 Torr favor the formation of Xe₂Cl*. Figure 3 also depicts the broadband emission of this trimer centered close to 500 nm. The intensities shown are not correct for the spectral response of the OMA model 1205D/01 vidicon detector, for which the sensitivity (counts/photon) drops by a factor of 5 from 500 to 308 nm.

III. FORMATION MECHANISM AND KINETICS OF THE Xe₂Cl EXCIMER

Previous studies have shown that fluorescence originating from both XeCl* and Xe₂Cl* is emitted when high density Ar/Xe/CCl₄ mixtures are excited by short duration pulses of 1 MeV electrons.^{1,5,12} Emission from XeCl* precedes that from Xe₂Cl*, and it has been suggested that XeCl* is a precursor in the reaction chain leading to the formation of Xe₂Cl*.^{7,13} In order to test this hypothesis, a model containing reactions for producing and removing Xe₂Cl* was constructed, and its predictions were compared with experimental observations. The model contained the following reactions:



A termolecular reaction was selected for the formation of Xe₂Cl* in order to keep the mechanism as simple as possible. This reaction is also the predominant formation mechanism for other Rg₂X* species.^{9,4,15} Preliminary experiments had shown that fluorescence from Xe₂Cl* was enhanced relative to that from XeCl* when the partial pressures of both Xe and Ar were increased. Therefore, the formation mechanism should contain both Xe and Ar. Reactions (2)–(5) were selected to represent loss of Xe₂Cl* by radiative decay and by collisions with various quenching gases.

The rate equation pertinent to the above mechanism can be written in the following form:

$$\frac{d}{dt} [\text{Xe}_2\text{Cl}^*] = k_1(\text{XeCl}^*)(\text{Xe})(\text{Ar}) - \frac{(\text{Xe}_2\text{Cl}^*)}{\tau}, \quad (6)$$

where *k*₁ is the termolecular rate constant and τ is the effective exponential decay constant for Xe₂Cl*, given by

$$\tau^{-1} = \tau_{500}^{-1} + k_{\text{CCl}_4}^{\text{q}}(\text{CCl}_4) + k_{\text{Xe}}^{\text{q}}(\text{Xe}) + k_{\text{Ar}}^{\text{q}}(\text{Ar}). \quad (7)$$

Here τ₅₀₀ is the radiative lifetime of Xe₂Cl* which emits at 500 nm, and *k*_{CCl₄}^q, *k*_{Xe}^q, and *k*_{Ar}^q are rate constants for the quenching of Xe₂Cl* by CCl₄, Xe, and Ar, respectively. In all of these expressions () denotes particle density in cm⁻³. Equation (6) can be converted to an expression containing *I*₃₀₈ and *I*₅₀₀, the fluorescent intensities of XeCl* and Xe₂Cl*, respectively, upon dividing the concentrations of XeCl* and Xe₂Cl* by the appropriate radiative lifetimes. After rearranging, the following equation is obtained¹⁶:

$$\frac{d}{dt} (I_{500}) = k_1(\text{Xe})(\text{Ar}) I_{308} \left(\frac{\tau_{308}}{\tau_{500}} \right) - \frac{I_{500}}{\tau}. \quad (8)$$

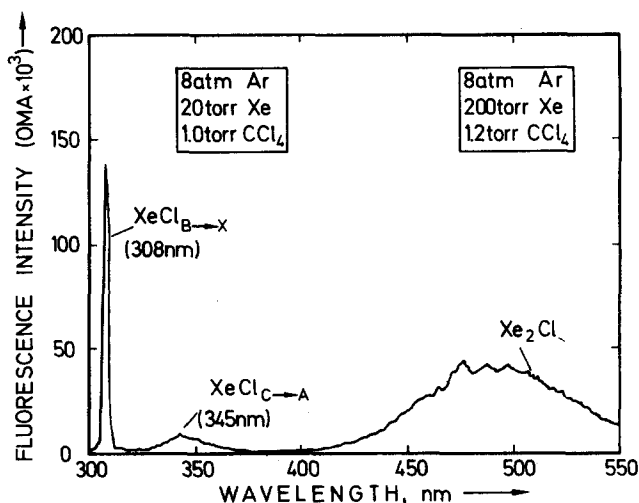


FIG. 3. Temporally integrated fluorescence spectrum of Xe₂Cl, XeCl (*B* → *X*), and XeCl (*C* → *A*).

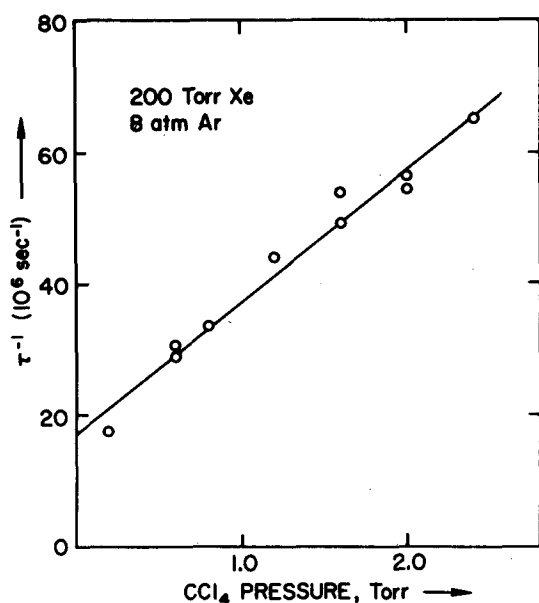


FIG. 4. The decay frequency of the Xe₂Cl* fluorescence at 500 nm as a function of CCl₄ pressure for mixtures containing fixed amounts of argon and xenon.

IV. EXPERIMENTAL RESULTS

Under all conditions investigated, the fluorescence emitted by XeCl at 308 nm was observed to decay much more rapidly than that emitted at 500 nm by Xe₂Cl. Therefore, the effective decay constant τ for Xe₂Cl could be measured by monitoring I_{500} after I_{308} had effectively decayed to zero. This allowed quenching studies to be made that were independent of the precise details of the Xe₂Cl formation mechanism.

The rate of collisional quenching of Xe₂Cl* by CCl₄ was established by measuring the decay constant τ for a number of mixtures containing constant amounts of Xe and Ar, but different amounts of CCl₄. Some of the experimental data are shown in Fig. 4. In this figure, the Xe₂Cl decay frequency τ is plotted as a function of the CCl₄ pressure for mixtures containing 200 Torr xenon and 8 atm argon. From the slope of Fig. 4, $k_{\text{CCl}_4}^q$ was calculated as $(6 \pm 1) \times 10^{-10} \text{ cm}^3 \text{ s}^{-1}$.

Collisional quenching of Xe₂Cl* by Xe and by Ar was studied in a manner similar to that described above. A change in τ was observed when the partial pressure of argon was varied between 1 and 8 atm in mixtures containing fixed amounts of Xe and CCl₄. From these measurements, a value of $(3 \pm 1) \times 10^{-14} \text{ cm}^3 \text{ s}^{-1}$ was estimated for k_{Ar}^q . An apparently systematic variation in τ was also observed when the partial pressure of Xe was varied from 50 to 400 Torr in mixtures containing 2 Torr of CCl₄ and 2 atom of argon. However, the magnitude of this variation was very small. Therefore, the value of $5 \times 10^{-13} \text{ cm}^3 \text{ s}^{-1}$ estimated for k_{Xe}^q from these measurements should be regarded only as an upper limit for this rate constant.

The radiative lifetime of Xe₂Cl* can be estimated from the zero pressure intercept in Fig. 4. This intercept contains contributions due to collisional quenching of Xe₂Cl* by Xe and by Ar. However, when these were

subtracted, as indicated by Eq. (7), $(\tau_{500})^{-1}$ was computed as $(7.5 \cdot 10^{-5}) \times 10^6 \text{ s}^{-1}$. The error in this value arises in part from the scatter in the data shown in Fig. 4. However, the main contribution arises from the uncertainty in our knowledge of k_{Xe}^q and k_{Ar}^q . The magnitude of the error reflects the fact that, in all of the mixtures studied, Xe₂Cl* was principally removed by collisions with CCl₄.

The Xe₂Cl formation mechanism was investigated by observing temporal fluorescence profiles using the fast photodiode and by recording the time-integrated spectrally resolved data taken by the optical multichannel analyzer. Qualitative predictions of the mechanism listed in the previous section were first verified; thereafter, calculations were performed in order to compare actual experimental data with quantitative predictions of the model.

Initially, Eq. (8) was used to analyze the temporal behavior of the fluorescence emitted by XeCl (*B-X*) at 308 nm, and by Xe₂Cl at 500 nm. Values of I_{500} and I_{308} were monitored using the photodiode in successive identical experiments, and were compared when I_{500} reached a maximum. At that instant the lhs of Eq. (8) is equal to zero, and the equation can be rearranged to yield

$$\frac{I_{500}}{I_{308}} = k_1(\text{Xe})(\text{Ar})\tau\left(\frac{\tau_{308}}{\tau_{500}}\right). \quad (9)$$

Two series of rare gas-halide mixtures were studied: one containing 2 Torr CCl₄, 2 atm Ar, and variable pressures of Xe ranging from 50 to 400 Torr, and another containing 2 Torr CCl₄, 8 atm Ar, and varying amounts of Xe ranging from 200 to 600 Torr. The effective decay constant τ for Xe₂Cl was measured in each experiment, and was found to be approximately constant, varying only by $\pm 12\%$. The ratio I_{500}/I_{308} was found to be linear in Xe partial pressure, and to be approximately four times greater in mixtures containing 8 atm Ar than in mixtures containing 2 atm argon.

In order to confirm this result based on temporal data, another series of experiments was performed. In these experiments, the total "time-integrated" fluorescence emitted throughout the experiment was measured using an optical multichannel analyzer (OMA). Using this device, time integrated fluorescence emitted by Xe₂Cl* at 500 nm, i.e., $\int I_{500} dt$, could be compared in the same experiment to that emitted by XeCl* at 308 nm. The mechanism outlined in the previous section predicts that the total amount of Xe₂Cl* formed per unit volume over the duration of the experiment is

$$k_1 \int_0^\infty (\text{XeCl}^*)(\text{Xe})(\text{Ar}) dt, \quad (10)$$

which can be rewritten as

$$k_1(\text{Xe})(\text{Ar})\tau_{308} \int I_{308} dt. \quad (11)$$

The fraction of Xe₂Cl* that emits radiation in the 500 nm band is (τ/τ_{500}) . Therefore, the total number of photons emitted by Xe₂Cl* in the 500 nm band throughout the experiment is

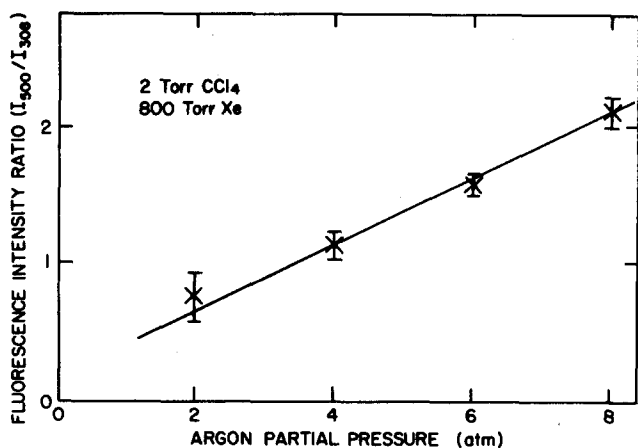


FIG. 5. The ratio of total fluorescence emitted by Xe₂Cl* at 500 nm to that emitted by XeCl* at 308 nm plotted against argon pressure for mixtures containing a fixed amount of CCl₄ and Xe. Each plotted point represents an average of four to eight experimental measurements. The error bars represent the standard deviation of each set of measurements.

$$\int I_{500} dt = k_1(\text{Xe})(\text{Ar})\tau(\tau_{308}/\tau_{500}) \int I_{308} dt. \quad (12)$$

Thus, the fluorescence ratio ($\int I_{500} dt / \int I_{308} dt$) is predicted to be linear in the partial pressure of xenon and argon.

Figure 5 displays the experimentally measured fluorescence ratio ($\int I_{500} dt / \int I_{308} dt$) as a function of the argon partial pressure in mixtures containing 2 Torr CCl₄ and 800 Torr Xe. Using the value of τ obtained from the photodiode experiments, the measured value of 135 ns for τ_{500} , and an estimated value of 16 ns⁷ for τ_{308} , k_1 was calculated from Eq. (12) as $(1.2 \pm 0.2) \times 10^{-31} \text{ cm}^6 \text{ s}^{-1}$.

Figure 6 shows the variation of experimentally measured fluorescence ratio with xenon partial pressure. As can be seen, the ratio is linear in the partial pressure of xenon in mixtures containing both 8 atm argon and 2 atm argon. The constant k_1 was estimated from the slopes of Fig. 6 as $(1.5 \pm 0.1) \times 10^{-31} \text{ cm}^6 \text{ s}^{-1}$ using the 8 atm mixtures and as $(1.6 \pm 0.2) \times 10^{-31} \text{ cm}^6 \text{ s}^{-1}$ using the 2 atm mixtures.

The linearity of the fluorescence ratio with both xenon and argon and the near identity between the rate constant obtained from Figs. 5 and 6 provides strong evidence in favor of the proposed mechanism, although the slight nonzero intercept displayed by the 2 atm data may be statistically significant, and may represent a slight contribution from another Xe₂Cl* source. Further evidence in support of the termolecular formation model was obtained by comparing the experimental Xe₂Cl fluorescence profile with that obtained by numerically integrating the rate equation pertinent to the proposed Xe₂Cl* formation mechanism using Euler's method with a step size of $\sim 4 \times 10^{-11} \text{ s}$. The concentration of XeCl* was calculated from the intensity of the experimentally measured XeCl (*B-X*) fluorescence, and was used as input data into the calculation. The input took the form of an array of 512 successive intensity measurements

recorded by the transient digitizer over a total time interval of 20 or 50 ns. The radiative lifetime of Xe₂Cl* was taken as 135 ns, and the rate constants for the various quenching reactions were chosen as $k_{\text{CCl}_4}^q = 6.0 \times 10^{-10} \text{ cm}^3 \text{ s}^{-1}$, $k_{\text{Xe}}^q = 5.0 \times 10^{-13} \text{ cm}^3 \text{ s}^{-1}$, and $k_{\text{Ar}}^q = 3.0 \times 10^{-14} \text{ cm}^3 \text{ s}^{-1}$ in order to fit the quenching data described previously. The termolecular rate constant k_1 was taken to be $1.5 \times 10^{-31} \text{ cm}^6 \text{ s}^{-1}$. In order to better compare theory with experiment, the computed values were multiplied by a scaling factor in order to adjust the maximum of the computed I_{500} profile to that of the experimental one. This factor varied from 0.8 to 1.3. For comparison, it should be noted that the peak fluorescence measured in "identical" experiments varied by as much as 15%.

Temporal profiles of Xe₂Cl fluorescence were calculated using the postulated mechanism for a wide variety of CCl₄/Xe/Ar mixtures ranging from 2 Torr CCl₄, 50 Torr Xe, and 2 atm Ar, to 10 Torr CCl₄, 600 Torr Xe, and 8 atm Ar. Two comparisons between calculation and experiment are shown in Figs. 7(a) and 7(b). Equally good comparisons were obtained for all other mixtures studied, except for one, in which superradiance occurred in the XeCl (*B-X*) transition, thus destroying the linear relationship between emission intensity and emitter concentration. The overall degree of agreement between calculation and experiment was excellent and strongly confirms the validity of the proposed Xe₂Cl* formation mechanism.

V. CONCLUSIONS

In this paper fluorescence experiments have been described that reveal some of the details concerning the formation and quenching of the triatomic excimer Xe₂Cl* which is produced by short duration electron beam pulse excitation of Ar/Xe/CCl₄ mixtures. It has been demonstrated that Xe₂Cl* is formed primarily in a termolecular reaction involving the diatomic excimer

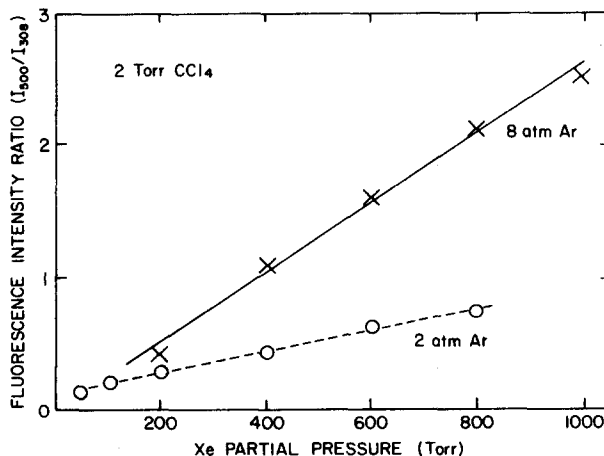


FIG. 6. The ratio of total fluorescence emitted at 500 nm to that emitted at 308 nm plotted as a function of Xe partial pressure. All measurements were made using mixtures containing 2 Torr CCl₄. The lower series of points refers to mixtures containing 2 atm Ar, the upper to mixtures with 8 atm of Ar.

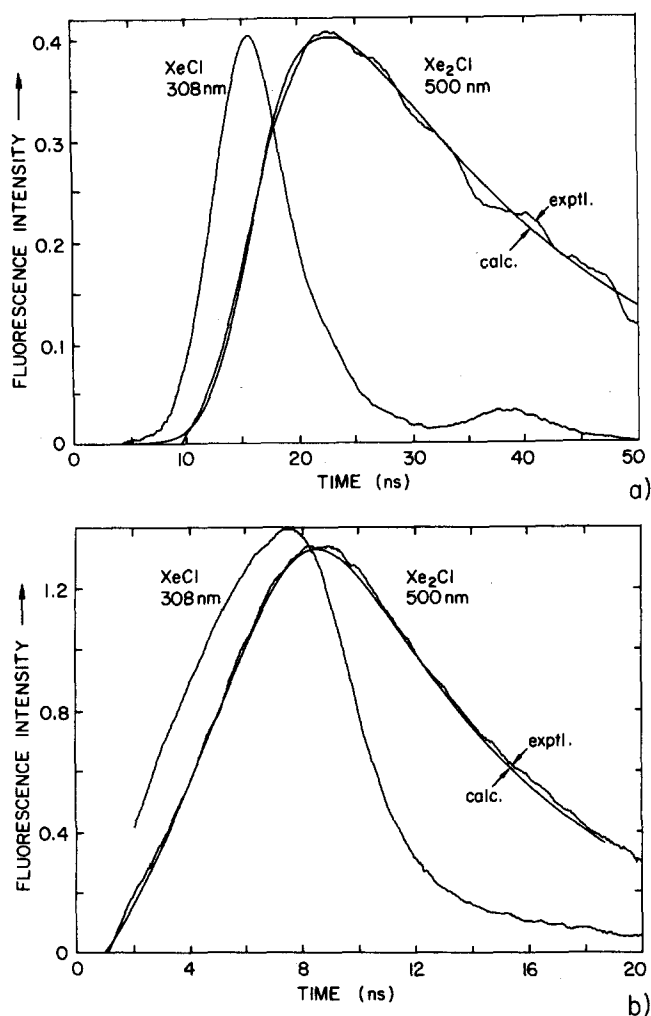


FIG. 7. Observed and calculated time dependence of XeCl ($B \rightarrow X$) and Xe₂Cl fluorescence (a) for a mixture of 2 atm Ar, 400 Torr Xe, 2 Torr CCl₄ and (b) 8 atm Ar, 600 Torr Xe, and 10 Torr CCl₄.

XeCl*. Rate constants for the formation reaction and for several bimolecular quenching reactions of Xe₂Cl* have been measured. In addition, the radiative lifetime of Xe₂Cl* has been estimated. A summary of these rate constants is given in Table I. The rate constants and radiative lifetime determined in Refs. 8 and 10 are consistent with the values determined in this work. The

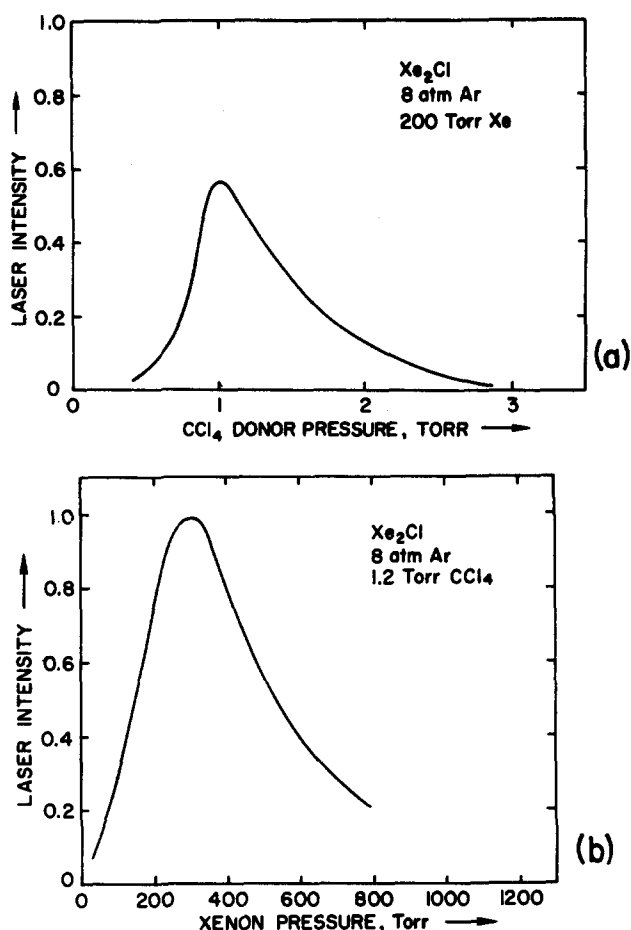


FIG. 8. Laser intensity as a function of CCl₄ halogen donor pressure and xenon pressure. The intracell resonator consisted of a spherical end reflector ($r=1$ m, $R>99\%$) and a flat output coupler ($R=98\%$) spaced 10 cm apart.

data of Tang *et al.* and Grieneisen *et al.* support a value for the radiative lifetime of Xe₂Cl* of 210 ± 20 and 185 ± 10 ns, respectively.

It is clear, on the basis of the results presented in Table I, that quenching by CCl₄ is the dominant loss process in the Xe₂Cl laser system. Quenching by argon and by xenon is less severe. Quenching conditions play an important role in determining laser operating characteristics. This fact is well illustrated in Fig. 8. As

TABLE I. Summary of Xe₂Cl* rate constants.

Reaction	Rate constant	Other work
(1) XeCl* + Ar + Xe → Xe ₂ Cl* + Ar	$k_1(\text{Ar, Xe}) = (1.5 \pm 0.5) \times 10^{-31} \text{ cm}^6 \text{ s}^{-1}$	$7.3 \times 10^{-31} \text{ cm}^6 \text{ s}^{-1}$ for Xe buffer ^a
(2) Xe ₂ Cl* → 2Xe + Cl + $h\nu$ (500 nm)	$\tau_{500} = 135 (+70-60) \text{ ns}$	120 ns, ^b 210 ns, ^a 185 ns ^c
(3) Xe ₂ Cl* + CCl ₄ → Quenching	$k_{\text{CCl}_4}^q = (6 \pm 1) \times 10^{-10} \text{ cm}^3 \text{ s}^{-1}$	$5 \times 10^{-10} \text{ cm}^3 \text{ s}^{-1}$ for Cl ₂ , ^a $2.6 \times 10^{-10} \text{ cm}^3 \text{ s}^{-1}$ ^c
(4) Xe ₂ Cl* + Ar → Quenching	$k_{\text{Ar}}^q = (3 \pm 1) \times 10^{-14} \text{ cm}^3 \text{ s}^{-1}$	
(5) Xe ₂ Cl* + Xe → Quenching	$k_{\text{Xe}}^q < 5 \times 10^{-13} \text{ cm}^3 \text{ s}^{-1}$	$< 4 \times 10^{-14} \text{ cm}^3 \text{ s}^{-1}$, ^a $6 \times 10^{-15} \text{ cm}^3 \text{ s}^{-1}$ ^c

^aReference 8.

^bReference 12.

^cReference 10.

can be seen, the effective pressure range for CCl₄ and xenon in this system is limited. Two alternate halogen donors (Cl₂ and HCl) were found to inhibit laser action in the present experimental arrangement.

The postulated mechanism predicts a very high efficiency for production of Xe₂Cl* from XeCl*. The production efficiency increases at high argon pressures, reaching a value of 60% at 15 atm argon. To date, however, the laser output power has been limited by the presence of transient molecular and atomic absorptions induced by electron beam pumping.^{5,6} The delayed appearance of the Xe₂Cl laser output shown in Fig. 2 is caused by the initial transient argon buffer gas absorption.¹⁷ In addition, atomic absorptions from xenon metastables to Rydberg states lead to considerable reduction of the laser output.

ACKNOWLEDGMENTS

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¹⁶In the interest of brevity, *I* has been expressed as a photon flux. Conversion to an energy flux requires multiplication by the photon energy $h\nu$.

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